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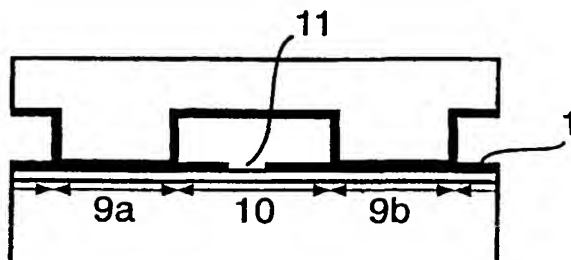
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(54) Title: MICRO-CONTACT PRINTING METHOD



(57) Abstract: The invention relates to micro-contact printing, wherein a self-assembled monolayer(SAM)-forming molecular species (1) is applied to a surface (2) of an article (3). The SAM-forming species (1) comprise a polar functional group that is exposed when the species (1) form a monolayer. This enables said printing method to be performed in vacuum or in a gaseous atmosphere, preferably in air. The invention also relates to an article having a surface comprising at least one isolated region of a SAM having a lateral dimension within the range of from 1 to 100 nm. Furthermore, the invention relates to a method for producing at least one nanowire, or a grid of nanowires, having a lateral dimension within the range of from 1 to 100 nm.